

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:  
Osamu Komuro, et al.

Application No.: Not Yet Assigned

Group Art Unit: N/A

Filed: Herewith

Examiner: Not Yet Assigned

For: PROCESS CONDITIONS CHANGE  
MONITORING SYSTEMS THAT USE  
ELECTRON BEAMS, AND RELATED  
MONITORING METHODS

PRELIMINARY AMENDMENT

Commissioner for Patents  
Washington, DC 20231

Dear Sir:

Preliminary to examination, please amend the above-referenced application as follows:

IN THE SPECIFICATION:

Rewrite the paragraphs at page 9, line 12 through line 19, as follows:

Figs. 4(a) through 4(c) are diagrams showing an example of patterns suitable for process conditions change monitoring.

Figs. 5(a) through 5(c) are cross-sectional views showing an example of patterns suitable for process conditions change monitoring.

Figs. 6(a) and 6(b) are graphs showing changes in edge width against focus.